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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/006,704	12/10/2001	Shane J. Trapp	M4065.0369/P369-A	3229
24998	7590 01/29/2003			
DICKSTEIN SHAPIRO MORIN & OSHINSKY LLP 2101 L STREET NW			EXAMINER	
	ON, DC 20037-1526		UMEZ ERONINI, LYNETTE T	
			ART UNIT	PAPER NUMBER
			1765	(į
			DATE MAILED: 01/29/2003	7

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)	- b			
		10/006,704	TRAPP, SHANE J.				
	Office Action Summary	Examiner	Art Unit				
		Lynette T. Umez-E	ronini 1765				
	The MAILING DATE of this communi	cation appears on the cover sl	eet with the correspondence addres	s			
Period fo		DD DEDLY 10 OFT TO EVDIE	E AMONITU(S) EDOM				
THE N - Exter after - If the - If NO - Failu - Any r earne	ORTENED STATUTORY PERIOD FOMALLING DATE OF THIS COMMUNII sions of time may be available under the provisions SIX (6) MONTHS from the mailing date of this comm period for reply specified above is less than thirty (3f period for reply is specified above, the maximum stare to reply within the set or extended period for reply eply received by the Office later than three months and patent term adjustment. See 37 CFR 1.704(b).	CATION. of 37 CFR 1.136(a). In no event, however unication.)) days, a reply within the statutory minimu tutory period will apply and will expire SIX will by statute cause the application to be	may a reply be timely filed m of thirty (30) days will be considered timely. (6) MONTHS from the mailing date of this communicome ABANDONED (35 U.S.C. § 133).	nication.			
Status	Described to a communication (a) file	od on					
1)	Responsive to communication(s) file	ed on 2b)⊠ This action is non-fina					
2a)☐	This action is FINAL . Since this application is in condition	, 		erits is			
3)	closed in accordance with the pract	ice under <i>Ex parte Quayle</i> , 19	35 C.D. 11, 453 O.G. 213.	Sillo io			
-	ion of Claims						
	Claim(s) 26-35 is/are pending in the						
	4a) Of the above claim(s) is/a	re withdrawn from considerati	on.				
5)	Claim(s) is/are allowed.						
6)⊠	6)⊠ Claim(s) <u>26-31,33 and 34</u> is/are rejected.						
•	Claim(s) 32 and 35 is/are objected to						
	Claim(s) are subject to restrict	tion and/or election requireme	ent.				
	ion Papers	- Francisco					
	The specification is objected to by the		to by the Evaminer				
10)	The drawing(s) filed on is/are: Applicant may not request that any obj	a) accepted of b) objected	n abevance See 37 CFR 1.85(a).				
44)[]	The proposed drawing correction file	ection to the drawing(s) be need.	b) ☐ disapproved by the Examiner.				
	If approved, corrected drawings are re						
12\[7	The oath or declaration is objected to						
•	under 35 U.S.C. §§ 119 and 120	•					
	Acknowledgment is made of a claim	for foreign priority under 35 l	J.S.C. § 119(a)-(d) or (f).				
	☐ All b)☐ Some * c)☐ None of:						
a,	1. Certified copies of the priority	documents have been receiv	ed.				
	2. Certified copies of the priority documents have been received in Application No.						
*	3 ☐ Copies of the certified copies	of the priority documents hav	e been received in this National Sta .2(a)).	ge			
44)	Acknowledgment is made of a claim	for domestic priority under 35	U.S.C. § 119(e) (to a provisional ap	plication).			
	a) The translation of the foreign la	nguage provisional application	has been received.				
15)	Acknowledgment is made of a claim	for domestic priority under 35	U.S.C. §§ 120 and/or 121.				
Attachme		νШ.	nterview Summary (PTO-413) Paper No(s).				
2) 🗍 Noti	ce of References Cited (PTO-892) ice of Draftsperson's Patent Drawing Review (rmation Disclosure Statement(s) (PTO-1449) I	>TO-948) 5) ☐ 1	lotice of Informal Patent Application (PTO-19)	52)			

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DETAILED ACTION

Claim Objections

1. Claims 32 and 35 are objected as being dependent respectively from canceled claims 24 and 36. Accordingly, the claims 32 and 35 have not been further treated on the merits.

Claim Rejections - 35 USC § 112

2. The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

3. Claims 27 and 33 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

In claim 27, lines 1-4, "... wherein said fluorocarbon is at least one member selected from the group consisting of carbon tetrafluoride, fluorohydrocarbons, ... and chlorofluorohydrocarbons" is indefinite because carbon tetrafluoride is a member of group of fluorocarbons. It is suggested to delete "carbon tetrafluoride."

4. Claim 33 provides for the use of "the composition of claim 26," where claim 33 recites "said composition is flowed into a reaction chamber containing said semiconductor device . . ." is indefinite because it is unclear what composition applicant is intending to encompass. It is suggested "said composition is flowed into a reaction chamber containing said semiconductor device such that" be deleted.

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Rejections - 35 USC § 102

5. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 6. Claims 26-31, 33, and 34 are rejected under 35 U.S.C. 102(b) as being anticipated by Hamrah (EP 0 553961 A2).

Hamrah teaches an etch chemistry of CHF₃, Ar, and CF₄ (page 2, line 16 and Abstract) in addition to a gaseous source of hydrogen, such as ammonia (page 2, lines 32-33 and Abstract), which reads on;

a gaseous mixture of at least one fluorocarbon and ammonia, as in claim 26;

at least one member selected from the group of fluorocarbons as recited in claims 27, 28, and 29;

at least two members selected from the group of said fluorocarbons as recited in claim 30.

Hamrah also teaches the flow rate of 30 sccm CHF₃ and 7 sccm ammonia (page 9, lines 2-5), which reads on a flow ratio of 30:7 (4:1) that encompasses the flow rate ratio of said fluorocarbon to said ammonia is not less than about 3:1, as **in claim 33**; and said flow rate ratio is within the range of about 3:1 to about 20:1 as **in claim 34**.

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Claim Rejections - 35 USC § 103

7. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

8. Claim 31 is rejected under 35 U.S.C. 103(a) as being unpatentable over Hamrah (EP '961 A2) as applied to claim 26 above, and further in view of Becker et al. (US 6,015,760).

Hamrah differs only in failing to teach wherein said fluorocarbon is a combination of CF₄, CHF₃ and CH₂F₂.

Becker teaches anisotropic etching takes place primarily in the vertical direction so that feature widths substantially match the photoresist pattern widths (column 1, lines 40-43); and anisotropic etching is utilized when feature sizing after etching must be maintained within specific limits so as not to violate alignment tolerances or design rules (column 1, line 43-46); and selectively etching SiO₂ layer with respect to a nitride layer by using a fluorinated chemical etchant system that comprises: CF₄, CHF₃ and a CH₂F₂ additive material (column 4, lines 16-18) and "in this way, the etching process provides for the formation of sidewalls in etched layers which have a substantially vertical profile (column 4, lines 29-31).

It is the examiner's position that it would have been obvious to one having ordinary skill in the art at the time of the claim invention to modify Hamrah's etchants by combining the etchants as taught by Becker for the purpose meeting specific limits that

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would not violate alignment tolerances or design rules design rules (Becker, column 1,

lines 43-46).

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Lynette T. Umez-Eronini whose telephone number is

703-306-9074. The examiner is normally unavailable on the First Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Benjamin Utech can be reached on 703-308-3836. The fax phone numbers

for the organization where this application or proceeding is assigned are 703-972-9310

for regular communications and 703-972-9311 for After Final communications.

Itue

January 23, 2003

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